Epitaxial p-type Copper Iodide Thin Films with controlled Carrier Concentration grown by Pulsed Laser Deposition

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Copper iodide is a wide-bandgap, naturally p-type semiconductor with high transparency in the visible spectral range and high hole mobility up to 44 cm²/Vs [1]. Although sputtered CuI thin films using an external iodine vapour source reached unprecedented electrical p-type conductivity, and high rectification ratio of junctions with n-ZnO, and large Seebeck coefficient [2, 3], a wide-range control of the hole concentration as prerequisite for advanced device applications remains difficult.

Pulsed Laser Deposition (PLD) has proven to be a surprisingly simple and efficient growth method for high-quality CuI thin films with controlled hole concentration, without the requirement of an extra iodine supply [4]. Various doping concentrations for example with selenium could be obtained using one single elliptically segmented PLD target [5]. From a diffusion study of PLD CuI films with oxygen deficient or oxygen saturated Al₂O₃ capping layers we found evidence for oxygen being a dominant shallow acceptor in CuI films [6]. Single-crystalline CuI films with only one rotational domain could be in-situ grown using lattice-matched NaBr buffer layers on SrF₂(111) substrates [7]. Due to the high water solubility of NaBr, free-standing μm-thin CuI with high crystalline quality could be easily prepared by a simple lift-off strategy [8].

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